

## Comparison Between the $\mu$ XPS Endstation and the PHI Quantum 2000

A. L. Johnson<sup>1,2</sup>, G. D. Ackerman<sup>1</sup>, M. R. Howells<sup>1</sup>, Z. Hussain<sup>1</sup>, H. A. Padmore<sup>1</sup>, T. R. Renner<sup>1</sup>, W. Steele<sup>1</sup>, F. Gozzo<sup>2</sup>, B. Triplett<sup>2</sup>, R. Ynzunza<sup>2</sup>, P. D. Kinney<sup>3</sup>, R. Odom<sup>4</sup>, E. Principe<sup>4</sup>

<sup>1</sup>Lawrence Berkeley National Laboratory, Advanced Light Source, Berkeley, CA

<sup>2</sup>Intel Corporation, Santa Clara CA

<sup>3</sup>MicroTherm LLC, Minneapolis, MN

<sup>4</sup>Charles Evans and Associates, Redwood City, CA

Comparison between analytical instruments allow relative cost/benefit analysis and guides one in optimizing both instruments. We have engaged in comparative studies of the PHI Quantum 2000 (Q2000) and the  $\mu$ XPS endstation at the ALS. Both machines are scanned probe imaging XPS systems (the Q2000 scans the X-ray beam and  $\mu$ XPS scans the sample). Further, the electron analyzer in both facilities are of very similar design.

The design goal of  $\mu$ XPS was to get the greater (resolution)x(intensity) product obtainable using a synchrotron radiation X-ray source.  $\mu$ XPS has higher resolution (1-2 $\mu$ ) at a power level roughly commensurate with the flux delivered by the Quantum 2000 at 100 $\mu$  resolution (table 1). The synchrotron source allows for variation of the photon energy - making photon energy dependent phenomena (NEXAFS, for example) accessible contrast/analytical tools. The disadvantage of the synchrotron source is the greater difficulty in accessing the facility and variation of the flux with time and energy.  $\mu$ XPS is still being improved (recently the flux was improved 50% from the reported values - design goals are 2-4x more flux and 1 $\mu$  resolution), but the following results reported here are useful as an interim baseline.

Energy resolution in  $\mu$ XPS is limited by the monochromator and the analyzer - we have similar resolution to the Q2000 at 500eV photon energy. The utility of this resolution for complex systems typical of industrial and environmental samples will be determined by the ability to deal with sample charging and heterogeneity. A small spot makes charge neutralization more difficult but makes it more likely that the sampled volume is homogeneous.

Scattered light determines the signal to noise of spectra of minority species in small regions. The  $\mu$ XPS optics are more demanding than the Q2000, and the scattered light results are worse. This issue may be addressed with improved optics and/or through software.

Instrument productivity (throughput) are influenced by other factors than flux and resolution - the ease of sample introduction, data analysis, and software overheads all play a part. The Q2000 has a highly developed user interface, and is a model to us of user friendliness. The overhead values in the figure are typical results obtained by skilled workers on  $\mu$ XPS and the Q2000 with average samples. This table indicates areas in need of improvement on  $\mu$ XPS: the longer overhead for imaging is being addressed by specialized hardware, the long time necessary to find regions of interest is being addressed by prefiducialization of the samples, and the handling overhead can be minimized by loading multiple sample cassettes at one time.

Stability of the instrument can be broken into issues common to both XPS devices and those specific to  $\mu$ XPS. Samples are positioned in  $\mu$ XPS by a mechanical stage. We installed a laser interferometer and will incorporate it into the control loop to improve scan accuracy. The stability of the  $\mu$ XPS source must be monitored by using reference channels in the data acquisition, and the reference incorporated into the data analysis.

## Comparison of $\mu$ XPS and PHI Quantum 2000

	$\mu$ XPS	Quantum 2000
<b>Signal Intensity</b>	Sputtered Ag ~33pA @ <u>1.5<math>\mu</math>m</u> spot size ~65kc/s 3d 5/2 (850eV hv, 300mA) (80,40) $\mu$ m slits, 23.5eV pass energy	Sputtered Ag ~50pA @ <u>100<math>\mu</math>m</u> spot size 90kc/s 3d 5/2 (1487 hv) 23.5eV pass energy
<b>Spectral Resolution</b>	Sputtered Ag 500eV hv 0.67 eV 870eV hv 1.03 eV 1250eV hv 1.68 eV (80,40) $\mu$ m slits, 23.5eV pass energy	Sputtered Ag 1486.6eV hv 0.64eV 23.5eV pass energy
<b>Spatial Resolution</b>	1x1.5 $\mu$ m	8 $\mu$ m
<b>Scattered Light</b>	~15%	~10% @ 2 x FWHM ~2% @ 5 x FWHM
<b>Handling Overhead</b>	15-30 minutes (dependent on sample vacuum characteristics)	10-15 minutes (dependent as $\mu$ XPS)
<b>Localization Overhead</b>	15-30 minutes (dependent on size and visibility of features)	20-30 minutes (dependent as $\mu$ XPS)
<b>Spectral Overhead</b>	6 minutes for 100x100 image spectra as Q2000	seconds for imaging ~1-2 minutes/spectra
<b>Data Reduction</b>	~10 minutes (conversion and analysis time)	5-10 minutes
<b>Spatial Reproducibility</b>	0.2-1 $\mu$ m with an image 1 $\mu$ m with an experiment <10 $\mu$ m linearity over 40x40mm sample	5-10 $\mu$ m
<b>Spectral Reproducibility</b>	Low (due to varying beam current, damage, etc.) - to be improved	Medium (due to sample damage and source drift)

**Table 1**

### ACKNOWLEDGMENTS

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## **REFERENCES**

1. E. Principe, R. W. Odom, Z. Hussain, and, H. Padmore, Proceedings of the 1998 MRS Spring Meeting, San Francisco, CA (submitted).

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Spokesperson for the micro-XPS PRT is Baylor Triplett, Intel Corporation, SC1-3, 3065 Bowers Ave, Santa Clara, CA 95052-8126 Baylor\_B\_Triplett@ccm.sc.intel.com